

IN THE CLAIMS

Please amend the claims as follows:

Claim 1 (Canceled).

Claim 2 (Currently Amended): ~~The semiconductor device according to claim 1, A~~
semiconductor device comprising:

an SOI substrate having a semiconductor substrate, an insulating layer, and a
semiconductor layer of a first conductivity type that are stacked in this order;

element isolation insulating films formed partially in a main surface of said
semiconductor layer, with portions of said semiconductor layer interposed between said
insulating layer and bottom surfaces of said element isolation insulating films;

a gate structure formed partially on said main surface of said semiconductor layer in
an element formation region defined by said element isolation insulating films;

a pair of recesses formed in said element formation region, said recesses being formed
in said main surface of said semiconductor layer in portions that are not covered by said gate
structure, with a channel formation region under said gate structure interposed between said
pair of recesses; and

source/drain regions formed in bottom surfaces of said recesses and having a second
conductivity type that is different from said first conductivity type, said source/drain regions
forming a pair, with said channel formation region interposed therebetween, and having
bottom surfaces or depletion layers that reach said insulating layer,

wherein a side surface of one recess of said pair of recesses makes an angle larger
than 90° with a part of said main surface of said semiconductor layer on which said gate
structure resides,

wherein the part of said main surface of said semiconductor layer ~~[[where]]~~ on which said gate structure resides forms an angle larger than 90° with a corresponding side surface of each said recess.

Claim 3 (Canceled).

Claim 4 (Currently Amended): ~~The semiconductor device according to claim 1,~~ A semiconductor device comprising:

an SOI substrate having a semiconductor substrate, an insulating layer, and a semiconductor layer of a first conductivity type that are stacked in this order;

element isolation insulating films formed partially in a main surface of said semiconductor layer, with portions of said semiconductor layer interposed between said insulating layer and bottom surfaces of said element isolation insulating films;

a gate structure formed partially on said main surface of said semiconductor layer in an element formation region defined by said element isolation insulating films;

a pair of recesses formed in said element formation region, said recesses being formed in said main surface of said semiconductor layer in portions that are not covered by said gate structure, with a channel formation region under said gate structure interposed between said pair of recesses; and

source/drain regions formed in bottom surfaces of said recesses and having a second conductivity type that is different from said first conductivity type, said source/drain regions forming a pair, with said channel formation region interposed therebetween, and having bottom surfaces or depletion layers that reach said insulating layer,

wherein said source/drain regions comprise:

first impurity-introduced regions having a relatively low concentration and formed in said main surface of said semiconductor layer; and

second impurity-introduced regions having a relatively high concentration and formed deeper than said first impurity-introduced regions,

wherein a depth from said main surface of said semiconductor layer to said bottom surface of each said recess is smaller than a depth from said main surface of said semiconductor layer to a bottom surface of each said first impurity-introduced region.

Claim 5 (Original): The semiconductor device according to claim 4,

wherein said source/drain regions further comprise third impurity-introduced regions formed in said main surface of said semiconductor layer, reaching a depth shallower than a depth of said second impurity-introduced regions.

Claim 6 (Currently Amended): ~~The semiconductor device according to claim 1,~~ A semiconductor device comprising:

an SOI substrate having a semiconductor substrate, an insulating layer, and a semiconductor layer of a first conductivity type that are stacked in this order;

element isolation insulating films formed partially in a main surface of said semiconductor layer, with portions of said semiconductor layer interposed between said insulating layer and bottom surfaces of said element isolation insulating films;

a gate structure formed partially on said main surface of said semiconductor layer in an element formation region defined by said element isolation insulating films;

a pair of recesses formed in said element formation region, said recesses being formed in said main surface of said semiconductor layer in portions that are not covered by said gate

structure, with a channel formation region under said gate structure interposed between said pair of recesses; and

source/drain regions formed in bottom surfaces of said recesses and having a second conductivity type that is different from said first conductivity type, said source/drain regions forming a pair, with said channel formation region interposed therebetween, and having bottom surfaces or depletion layers that reach said insulating layer,

wherein said source/drain regions comprise:

first impurity-introduced regions having a relatively low concentration and formed in said main surface of said semiconductor layer;

second impurity-introduced regions having a relatively high concentration and formed deeper than said first impurity-introduced regions; and

third impurity-introduced regions formed in said main surface of said semiconductor layer,

wherein a depth from said main surface of said semiconductor layer to bottom surfaces of said third impurity-introduced regions is greater than a depth from said main surface of said semiconductor layer to bottom surfaces of said first impurity-introduced regions, and

wherein a depth from said main surface of said semiconductor layer to said bottom surfaces of said recesses is smaller than a depth from said main surface of said semiconductor layer to said bottom surfaces of said third impurity-introduced regions.

Claim 7 (Currently Amended): ~~The semiconductor device according to claim 1, A~~
semiconductor device comprising:

an SOI substrate having a semiconductor substrate, an insulating layer, and a semiconductor layer of a first conductivity type that are stacked in this order;

element isolation insulating films formed partially in a main surface of said semiconductor layer, with portions of said semiconductor layer interposed between said insulating layer and bottom surfaces of said element isolation insulating films;

a gate structure formed partially on said main surface of said semiconductor layer in an element formation region defined by said element isolation insulating films;

a pair of recesses formed in said element formation region, said recesses being formed in said main surface of said semiconductor layer in portions that are not covered by said gate structure, with a channel formation region under said gate structure interposed between said pair of recesses; and

source/drain regions formed in bottom surfaces of said recesses and having a second conductivity type that is different from said first conductivity type, said source/drain regions forming a pair, with said channel formation region interposed therebetween, and having bottom surfaces or depletion layers that reach said insulating layer,

wherein said gate structure comprises:

a gate insulating film formed on said main surface of said semiconductor layer;

a gate electrode formed on said gate insulating film; and

first sidewalls formed on sides of said gate electrode;

and wherein said semiconductor device further comprises:

second sidewalls formed on said bottom surfaces of said recesses and in contact with said first sidewalls; and

metal-semiconductor compound layers formed on said source/drain regions in portions that are not covered by said second sidewalls.

Claim 8 (Original): The semiconductor device according to claim 7, further comprising third sidewalls formed on said bottom surfaces of said recesses and being in contact with said element isolation insulating films,

wherein said metal-semiconductor compound layers are formed on said source/drain regions in portions that are not covered by said second and third sidewalls.

Claims 9-11 (Canceled).